

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

| | | |
|----------------|---|--|
| Applicant | : | Ogata et al. |
| Appl. No. | : | 10/589,681 |
| Filed | : | August 16, 2006 |
| For | : | POLYMER COMPOUND, PHOTORESIST COMPOSITION INCLUDING THE POLYMER COMPOUND, AND RESIST PATTERN FORMATION METHOD |
| Examiner | : | Chu, John S Y |
| Group Art Unit | : | 1795 |

RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **June 24, 2009**, please consider the following amendments and remarks:

Amendments to the Claims are reflected in the listing of claims begins on page 2 of this paper.

Remarks begin on page 8 of this paper.